

WHAT IS CLAIMED IS:

1. A process for fabricating a liquid crystal display, comprising the steps of:
 - a) preparing a substrate having a major surface;
 - b) patterning a first conductive material layer into plural gate layers and plural storage electrode layers on said major surface;
 - c) covering said plural gate layers and said plural storage electrode layers with a gate insulating layer;
 - d) patterning an amorphous silicon layer into plural amorphous silicon layers on said gate insulating layer;
 - e) selectively etching said gate insulating layer together with a piece of residual amorphous silicon connected between two of said plural amorphous silicon layers, if any, for forming contact slits in said gate insulating layer, a piece of conductive material between one of said plural gate layers and an adjacent storage electrode layer being exposed to one of said contact slits, if any;
 - f) patterning a second conductive material layer into plural drain layers and plural source layers, said piece of conductive material being split during the patterning of said second conductive material layer;
 - g) patterning a transparent material layer into pixel electrodes respectively held in contact with said plural source layers; and
 - h) completing said liquid crystal display.
2. The process as set forth in claim 1, in which one of said contact slits extends through a part of said gate insulating layer between one of said gate layers and adjacent one of said plural drain layers, another part of said gate insulating layer between said adjacent one of said plural drain layers and adjacent one of said plural storage electrode layers and yet another part of said gate insulating layer between one end portion of said part of said gate insulating layer and one end portion of said another part of said gate insulating layer opposed to said one end portion of said part.